

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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In re application of:  
Kajiwara, et al.

Serial No.  
Filed:

to be assigned  
herewith

Atty. Docket No. A-70092/RMA/WEN

**Chemical Mechanical Polishing Apparatus And  
Method Having A Retaining Ring with A  
Contoured Surface**

June 4, 2001

San Francisco, CA

INFORMATION DISCLOSURE STATEMENT

Assistant Commissioner for Patents  
Washington D.C. 20231

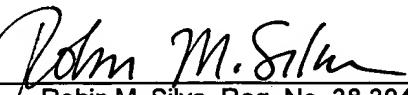
Sir:

Applicant hereby submits patents, publications, or other information of which he is aware, which he believes may be material to the examination of the above referenced application and in respect to which there may be a duty to disclose in accordance with 37 C.F.R. §1.56. The disclosure contained herein is not intended to constitute an admission that any patent, publication, or other information referred to is "prior art" for this invention unless specifically designated as such. In accordance with 37 C.F.R. §1.97 (b), the filing of this Information Disclosure Statement shall not be construed to mean that a search has been made or that no other material information as defined by 37 C.F.R. §1.56 exists.

No fee is due.

Respectfully submitted,  
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INFORMATION DISCLOSURE		ATTY. DOCKET NO. A-70092/RMAWEN	SERIAL NO. 1100
CITATION		APPLICANT Kajiwara, et al.	
PTO-1449		FILING DATE	GROUP

## U.S. PATENT DOCUMENTS

## FOREIGN PATENT DOCUMENTS

## OTHER PUBLICATIONS

EXAMINER	DATE CONSIDERED
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